

NIP-154

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

M. IZAWA et al

Serial No. 09/373,723

Group Art Unit: 1763

Filed: August 13, 1999

Examiner: L. Alejandro Mulero

For: A DRY ETCHING METHOD

#8  
7/24/01  
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REPLY TO ELECTION REQUIREMENT

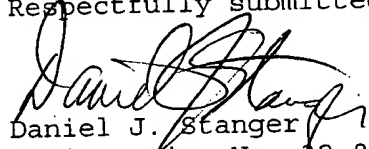
Commissioner for Patents  
Washington, D.C. 20231

July 20, 2001

Sir:

In reply to the Office Action mailed June 21, 2001,  
Applicants hereby elect the first embodiment directed to  
performing an etching treatment which generates fluorine  
radicals and CF<sub>2</sub> whereby the frequency of electromagnetic  
waves used in the etching process is in a range from 300-600  
MHz, on which claims 1-18 and 21 are readable.

Respectfully submitted,

  
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TC 1700 MAIL ROOM

JUL 24 2001

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Date: July 20, 2001